

[DOCUMENT] ABSTRACT

An object is to provide a mask blank that facilitates visual identification of the boundary between regions where a thin film is formed and not formed, and which facilitates positional adjustment of a masking plate to be provided on a sputtering apparatus for forming the thin film.

A mask blank having a substrate and a thin film, featured in that the substrate includes two main surfaces and a side surface with a chamfered surface provided between the two main surfaces and the side surface, one main surface of the two main surfaces includes an inner region including a center of the main surface and an outer peripheral region outside of the inner region, the thin film is provided on the inner region of the main surface, the surface reflectance R_s of the outer peripheral region with respect to light of 400nm to 700nm wavelength is 10% or less, and provided that R_f is the surface reflectance with respect to light of 400nm to 700nm wavelength in one section among sections of the thin film in the range of 9nm to 10nm film thickness, the contrast ratio (R_f/R_s) is 3.0 or more.